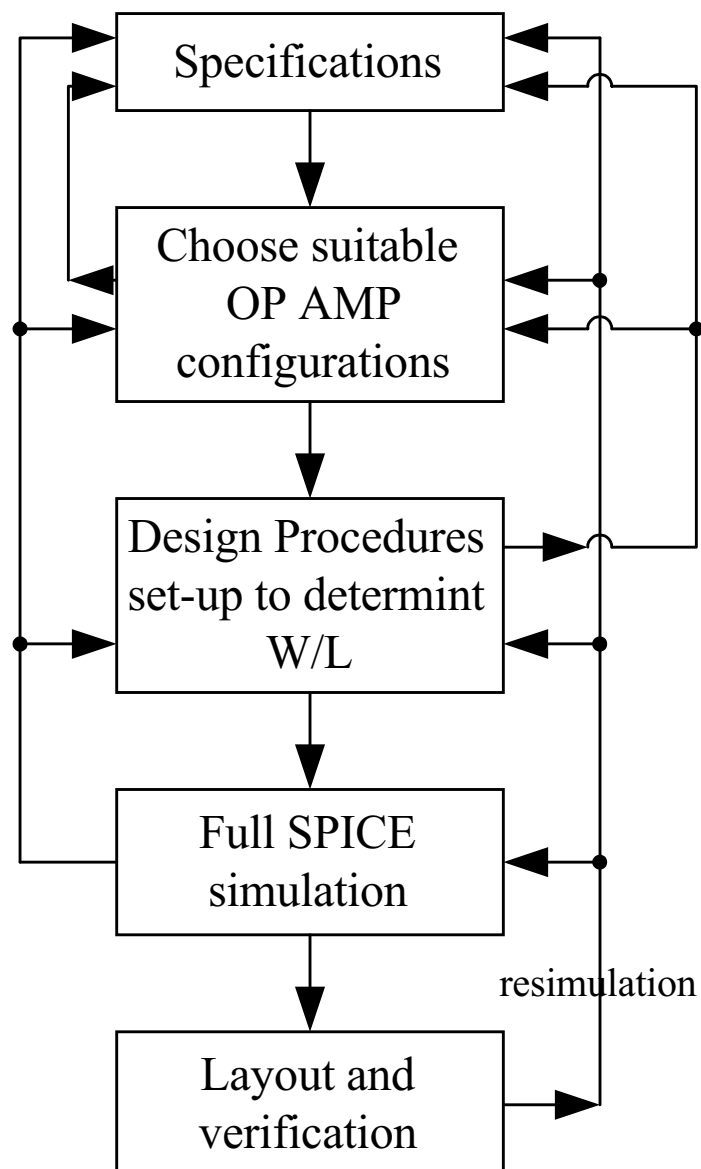


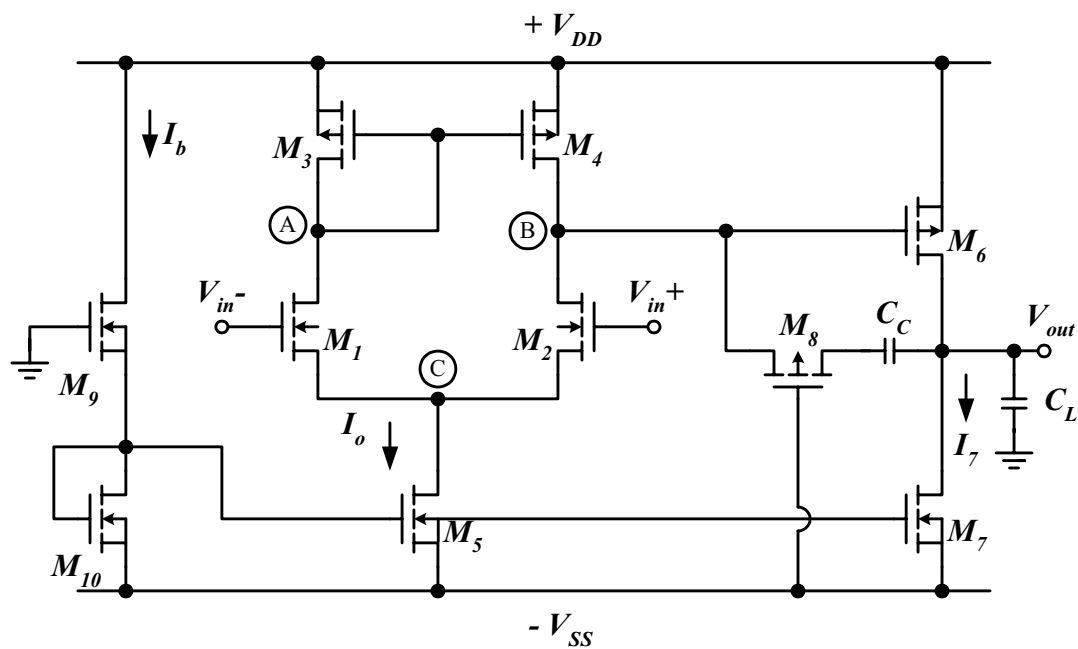
## Chapter 7 Design Procedure of CMOS OP AMPs and Practical Design Considerations on Noise and Offset

### § 7-1 Typical design procedure of two-stage CMOS OP AMPs

Synthesis or Design : Determine the circuit configuration and its MOS device dimensions from the specifications.

Flow Diagram :





### Specifications

Low frequency gain	$\geq 70\text{dB}$	Phase margin	$> 60^\circ$
Unity-gain frequency	$\geq 2\text{MHz}$	$C_L$	10pF
Slew rate	$\geq 4\text{V}/\mu\text{s}$	$V_{DD}=V_{SS}$	5V
CMRR	$\geq 80\text{dB}$		

### Device parameters

$\mu C_{\text{ox}}/2$	$30\mu\text{A}/\text{V}^2$	$12\mu\text{A}/\text{V}^2$
	(NMOS)	(PMOS)
$V_{\text{TO}}$	1.2V	-1V

### Procedures :

1. Choose a suitable  $C_c$

Example : choose  $C_c=C_L=10\text{pF}$

2. According to the phase margin in the specifications, determine the second pole position.

Example : choose  $f_T = 2\text{MHz}$

$$|S_{p2}| \cong + \frac{g_{m6}}{C_L} = 3\omega_u \cong 3g_{mi}/C_c$$

$$|S_{p2}| = 3\omega_u \Rightarrow \text{Phase margin} > 60^\circ$$

3. Determine the transconductances of the first stage and the second stage.

$$\text{Example : } g_{m6} = 3g_{mi} = 3\omega_u C_L = 3 \times 2\pi \times 2 \times 10^6 \times 10^{-11}$$

$$\Rightarrow g_{m6} = 377\mu \text{ mho}$$

$$g_{mi} = 125.7\mu \text{ mho}$$

4. From the slew rate specification, determine the bias currents in the first and the second stages.

$$\text{Example : } S = \frac{I_o}{C_c} \geq 4V/\mu s$$

$$\text{Choose } S = 4V/\mu s, \Rightarrow I_o = 40\mu A$$

The negative-going slew rate is also limited by the  $Q_7$  current source. To reduce or eliminate its effect,  $S_{ro}$  is set to 4S.

$$S_{ro} = 2.5S = 10V/\mu s = \frac{I_7}{C_L}$$

$$\Rightarrow I_7 = C_L S_{ro} = 100\mu A$$

5. Use the design rule for reducing the systematic offset voltage to design the transconductance of the load MOSFET's.

$$\text{Example : } \frac{(W/L)_3}{(W/L)_6} = \frac{(W/L)_4}{(W/L)_6} = \frac{I_o/2}{I_7} = \frac{1}{5}$$

$$g_{m1} = g_{m3} = g_{m4} = \sqrt{\frac{(W/L)_3 \cdot I_o/2}{(W/L)_6 \cdot I_7}} g_{m6}$$

$$= \frac{I_o/2}{I_7} g_{m6} = \frac{1}{5} g_{m6} \cong 75.4\mu \text{ mho}$$

6. Calculate  $A_{dm}$  and  $CMRR$  to verify the design.

$$\text{Example : } A_{dm} = \frac{g_{mi}g_{m6}}{(g_{d1} + g_{di})(g_{d6} + g_{d7})} \cong \frac{g_{mi}g_{m6}}{(\lambda_o)(2\lambda_7)}$$

$$\cong 6582 > 76dB \quad (\lambda = 0.03V^{-1} \text{ for } L \cong 10\mu m)$$

$$CMRR = 2 \frac{g_{mi}g_{ml}}{g_{d5}g_{di}} \approx \frac{2g_{mi}g_{ml}}{(\lambda_o)(\lambda_o/2)} \approx 26327 \approx 88dB$$

$$g_{mi} = C_c W_u, I_o = C_c S, g_{m6} = 3W_u C_L, I_7 = S_{ro} C_L$$

$$g_{ml} = I_o g_{m6} / 2I_7 = 3C_c S W_u / 2S_{ro}$$

$$\Rightarrow A_{dm} \approx \frac{3\omega_u^2}{2\lambda^2 S_{ro} S} \quad ; \quad CMRR \approx \frac{6\omega_u^2}{\lambda^2 S_{ro} S} \approx 4A_{dm}$$

If  $A_{dm}$  and  $CMRR$  could not satisfy the specifications,  
 $\omega_o$ ,  $S$ , and  $g_{mi}$  or  $g_{m6}$  can be readjusted .

7. Determine the nulling resistor  $R_c$  provided by  $M_8$ .

Example: If  $S_z \rightarrow S_{p2}$

$$R_c = \frac{1 + (C_d + C_L) / C_c}{g_{m6}} \approx \frac{2}{g_{m6}} \approx 5.3K\Omega$$

If  $S_z \rightarrow \infty$

$$R_c = \frac{1}{g_{m6}} = 2.65K\Omega$$

$$R_c = \frac{1}{\frac{\mu_p C_{ox}}{2} \frac{W_8}{L_8} [2(V_{SS} + V_B - |V_{TH8}|)]}$$

8. Dimension  $M_5$  and  $M_7$ .

$W/L$  can't be too small  $\Rightarrow$  too large  $V_{GS}$ .

Can't be too large  $\Rightarrow C_w$  too large  $\Rightarrow CMRR \downarrow$

$C_L \uparrow \Rightarrow$  phase margin  $\downarrow$

Example: 
$$\left(\frac{W}{L}\right)_5 = \frac{I_o}{\frac{\mu_n C_{ox}}{2} (V_{GS5} - V_{TH5})^2} \approx 5.33 \quad \left(\frac{\mu_n C_{ox}}{2} \approx 30 \mu A/V^2\right)$$

$$V_{GS5} - V_{TH5} \approx 0.5V$$

$$\left(\frac{W}{L}\right)_7 = \frac{I_7}{\frac{\mu_n C_{ox}}{2} (V_{GS7} - V_{TH7})^2} \approx 13.33$$

Choose  $L_5=L_7=10\mu m \Rightarrow W_5=54\mu m, W_7=133\mu m$

9. Dimension  $M_1-M_4$  and  $M_6$

Example: 
$$g_m \approx 2 \sqrt{\frac{\mu C_{ox}}{2} \left(\frac{W}{L}\right) i_D^0}$$

$$\left(\frac{W}{L}\right)_1 = \left(\frac{W}{L}\right)_2 \approx \frac{8m_i^2}{4 \frac{\mu_n C_{ox}}{2} I_o / 2} \approx 6.58$$

$$(W/L)_3 = (W/L)_4 \approx \frac{g_{m1}^2}{4 \frac{\mu_p C_{ox}}{2} I_o / 2} \approx 5.92$$

$$(W/L)_6 = 5(W/L)_3 \approx 29.6$$

Choose  $L=10 \mu m$

$$\Rightarrow W_1 = W_2 = 66 \mu m, W_3 = W_4 = 60 \mu m, W_6 = 300 \mu m$$

10. Estimate the dc bias voltage.

Example: 
$$|V_{GS3}| = |V_{THP3}| + \sqrt{\frac{I_o / 2}{\frac{\mu_p C_{ox}}{2} (W/L)_3}} = 1 + \sqrt{\frac{20}{12 \times 6}} \approx 1.527$$

$$\Rightarrow V_A = V_B = V_{DD} - |V_{GS3}| = 3.473V$$

$$\frac{I_o}{2} = \frac{\mu_n C_{ox}}{2} (W/L)_1 (-V_C - V_{THn})^2$$

$$\Rightarrow V_C = -1.518V$$

11. Dimension  $M_8$

$$\text{Example : } 2 \frac{\mu_p C_{ox}}{2} (W/L)_8 (5 + 3.473 - 1) = \frac{1}{R_C}$$

$$\Rightarrow (W/L)_8 \approx 1.052$$

choose  $W_8 = L_8 = 10 \mu m$ .

12. Determine  $V_{BIAS}$  and dimension  $M_9$  and  $M_{10}$

$$\text{Example : } V_{GS} = V_{THn} + 0.5V = 1.7V$$

$$V_{BIAS} = -V_{SS} + V_{GSS} = -3.3V$$

Choose  $I_b = 20 \mu A$

$$\Rightarrow V_{GS9} = 0 - V_{BIAS} = 3.3V \Rightarrow V_{BIAS} = -3.3V$$

$$V_{GS10} = V_{BIAS} + V_{SS} = -1.7V$$

$$(W/L)_9 = \frac{I_b}{\frac{\mu_n C_{ox}}{2} (V_{GS9} - V_{THn})^2} \approx 0.1512$$

$$(W/L)_{10} = \frac{I_b}{\frac{\mu_n C_{ox}}{2} (V_{GS10} - V_{THn})^2} \approx 0.2667$$

Choose  $W_9 = 10 \mu m$ ,  $L_9 = 66 \mu m$  and

$$W_{10} = 27 \mu m, L_{10} = 10 \mu m.$$

13. Use SPICE to simulate the overall OP AMP and make the necessary adjustment.

*Reference : Reference Book No. 3, (Gregorian and Temes) pp. 222-241.*

## §7-2 Practical Design Consideration on Noise

### §7-2.1 Noise of MOS devices

#### 1) shot noise

- \* Due to the fluctuation in the number of carriers crossing a given surface in the conductor in any time interval.
- \* If the carrier density is low and the external electric field is high so that the interaction among the carriers are negligible, we have

$$\overline{i_{ns}^2} = 2qI(BW)$$

where  $i_{ns}$  is the random variation of the current.

$I$  is the average current.

$BW$  is the bandwidth in which the noise is measured.

- \* When an MOSFET is operated in the saturation region, inversion carrier density is high.  $\Rightarrow \overline{i_{ns}^2}$  is much smaller than that predicted by the formula.

Shot noise is not important.

- \* In the subthreshold region, shot noise is higher.

#### 2) Thermal noise

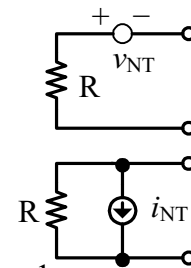
- \* Generated by the random thermal motion of the carriers in a resistor.
- \* The mean square of the noise voltage  $v_{nT}$  and the noise current  $i_{nT}$  are

$$\overline{v_{nT}^2} = 4KTR(BW)$$

$$\overline{i_{nT}^2} = 4KTG(BW)$$

- \* In MOSFETs,  $R$  is the incremental channel resistance.

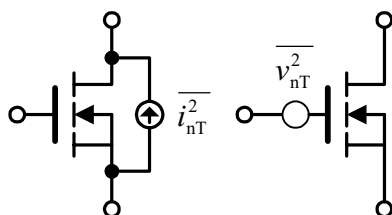
If the MOSFET is in the saturation region,  $R = \frac{3}{2g_m} = \frac{1}{\frac{2}{3}g_m}$



$$\overline{v_{nT}^2} = \left( \frac{i_{nT}}{g_m} \right)^2 = \frac{8}{3} \frac{KT}{g_m} BW$$

- \* The spectral density  $\overline{v_{nT}^2}/BW$  is independent of frequency  $\Rightarrow$  White noise.

- \* Circuit models:



$\overline{v_{nT}^2}$  : gate-referred noise voltage source.

$$* \sqrt{\frac{v_{nT}^2}{BW}} = \frac{nV}{\sqrt{H_z}}$$

\* When the MOSFET is turned off ( $R=\infty, G=0$ ),  $\overline{i_{nT}^2}$  is very small.

$\Rightarrow$  Noiseless open circuit.

### 3) Flicker ( $1/f$ ) noise

\* Generated by the trapping and releasing electrons from the channel caused by the interfacial states.

\* Slow process  $\Rightarrow$  important at low frequencies

$\Rightarrow 1/f$  noise. Below  $\sim$  KHz

$$* \overline{v_{nf}^2} = \frac{K}{C_{ox} WL} \frac{BW}{f} \quad \overline{i_{nf}^2} = g_m^2 \overline{v_{nf}^2}$$

\*  $(WL) \uparrow, C_{ox} \uparrow, \text{Temperature} \downarrow, \text{density of surface state} \downarrow \Rightarrow \overline{v_{nf}^2} \downarrow$

### 4) Combined noise

$$i_n = \sqrt{\overline{i_{nT}^2} + \overline{i_{nf}^2}} = \sqrt{(4KTG + Kg_m^2 / (C_{ox} WLf)) BW}$$

$\therefore$  independent noise sources.

$$v_n = \frac{i_n}{g_m}$$

## §7-2.2 Noise Performance of NMOS Amplifiers

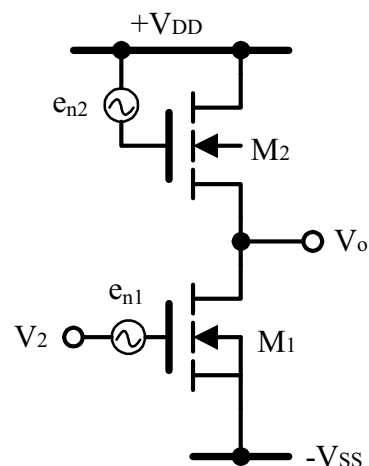
### 1) Enhancement-load amplifier

$$A_{V1} = -\alpha_2 \sqrt{\frac{W_1 L_2}{W_2 L_1}} \quad \text{for } e_{n1}$$

$$A_{V2} = \alpha_2 \quad \text{for } e_{n2}$$

The equivalent input noise voltage

$$\begin{aligned} e_n (\text{IN}) &= \frac{1}{A_{V1}} \sqrt{(A_{V1} e_{n1})^2 + (A_{V2} e_{n2})^2} \\ &= e_{n1} \sqrt{1 + \left(\frac{A_{V2} e_{n2}}{A_{V1} e_{n1}}\right)^2} \\ &= \sqrt{\frac{a_n}{W_1 L_1} \left(1 + \frac{L_1}{L_2}\right)^2} \end{aligned}$$



$e_n : 1/f$  noise

$$e_n = \sqrt{\frac{a_n}{WL}}$$

- \*  $W_1 \uparrow, L_2 \uparrow \Rightarrow$  smaller  $e_n$  (IN)
- \* There exists an optimal  $L_1 = L_2$  \* Independent of  $W_2$

§7-2.3 Noise Performance of CMOS Amplifiers

1) CMOS amplifier

$$A_{V1} = -g_{m1} (r_{ds1} \parallel r_{ds2})$$

$$A_{V2} = -g_{m2} (r_{ds1} \parallel r_{ds2})$$

$$g_{m1} = 2 \sqrt{\left(\frac{\mu_n C_{ox}}{2}\right)_1 \frac{W_1}{L_1} I_D}$$

$$g_{m2} = 2 \sqrt{\left(\frac{\mu_n C_{ox}}{2}\right)_2 \frac{W_2}{L_2} I_D}$$

$$e_n \text{ (IN)} = \sqrt{\frac{a_{n1}}{W_1 L_1} \left[ 1 + \frac{\left(\frac{\mu_p C_{ox}}{2}\right)_2 a_{n2}}{\left(\frac{\mu_n C_{ox}}{2}\right)_1 a_{n1}} \left(\frac{L_1}{L_2}\right)^2 \right]}$$

Design considerations for low noise can be found.

2) CMOS differential-input to single-ended converter

$$A_{V1} = \frac{1}{2} (g_{m1} + g_{m2}) (r_{ds1} \parallel r_{ds2}) \quad \text{for } e_{n1}, e_{n3}$$

$$A_{V2} = g_{m2} (r_{ds1} \parallel r_{ds2})$$

If  $g_{m1} = g_{m3}$  and  $g_{m2} = g_{m4}$

$$\Rightarrow e_n \text{ (IN)} = \sqrt{2 \frac{a_{n1}}{W_1 L_1} \left[ 1 + \frac{\left(\frac{\mu_n C_{ox}}{2}\right)_2 a_{n2}}{\left(\frac{\mu_p C_{ox}}{2}\right)_1 a_{n1}} \left(\frac{L_1}{L_2}\right)^2 \right]}$$

\*  $W_1 \uparrow, L_2 \uparrow, e_n$  (IN)  $\downarrow$

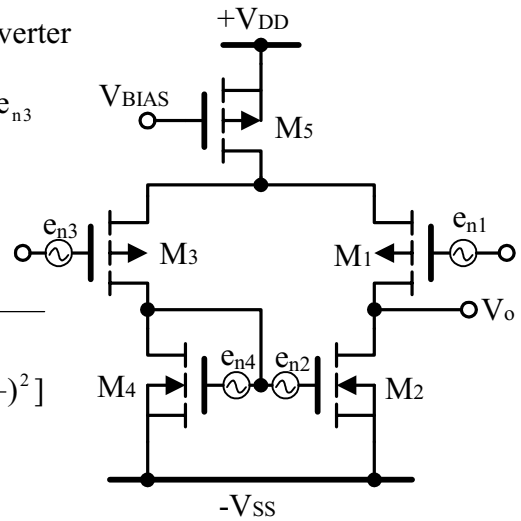
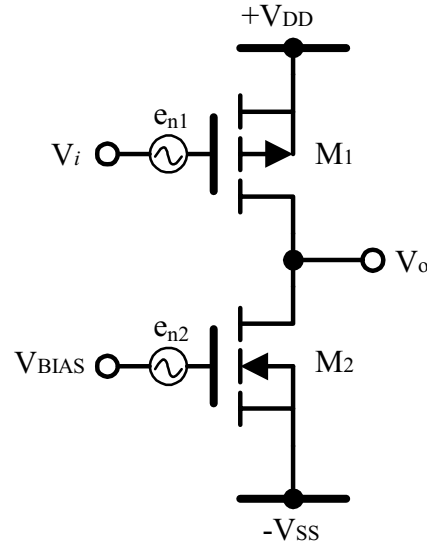
\* Optimal  $L_1 = \sqrt{\frac{\left(\frac{\mu_p C_{ox}}{2}\right)_1 a_{n1}}{\left(\frac{\mu_n C_{ox}}{2}\right)_2 a_{n2}}} L_2$

\* The noise from  $M_2$  and  $M_4$  loads is very important!

Example : PMOS :  $\left(\frac{\mu C_{ox}}{2}\right)_p = 3 \mu A / V^2$

$$a_{np} = 48 \times 10^3 (\mu V \cdot \mu m)^2 \quad \text{for } 20\text{Hz} \sim 20\text{KHz}$$

NMOS :  $\left(\frac{\mu C_{ox}}{2}\right)_N = 7 \mu A / V^2$



$$a_{nn} = 380 \times 10^3 (\mu\text{V} \cdot \mu\text{m})^2 \quad \text{for } 20\text{Hz} \sim 20\text{KHz}$$

\* NMOS is much more noisy than PMOS due to much larger  $\frac{1}{f}$  noise

Why? 1.higher surface-state density

2.nonuniform trap center distribution ( more centers near conduction band )

3.Efficient election trapping and releasing.

Bias current  $I_D = 5\mu\text{A}$ , Gain :  $\approx 44\text{dB}$

Design I :  $M_1, M_3 : \frac{500\mu\text{m}}{5\mu\text{m}}$  PMOS

$M_2, M_4 : \frac{100\mu\text{m}}{4\mu\text{m}}$  NMOS

$$\Rightarrow e_n(\text{IN}) = 38\mu\text{V} \quad 20\text{Hz} \sim 20\text{KHz} \quad (33.9)$$

Design I :  $M_1, M_3 : \frac{500\mu\text{m}}{5\mu\text{m}}$  PMOS

$M_2, M_4 : \frac{50\mu\text{m}}{44\mu\text{m}}$  NMOS

$$\Rightarrow e_n(\text{IN}) = 7.5\mu\text{V} \quad 20\text{Hz} \sim 20\text{KHz} \quad (6.9)$$

### 3) CMOS inverter amplifier

$$A_V \equiv \frac{V_o}{V_i} = (g_{m1} + g_{m2})(r_{ds1} \parallel r_{ds2})$$

$$A_{V1} = -g_{m1}(r_{ds1} \parallel r_{ds2}) \quad \text{for } e_{n1}$$

$$A_{V2} = -g_{m2}(r_{ds1} \parallel r_{ds2}) \quad \text{for } e_{n2}$$

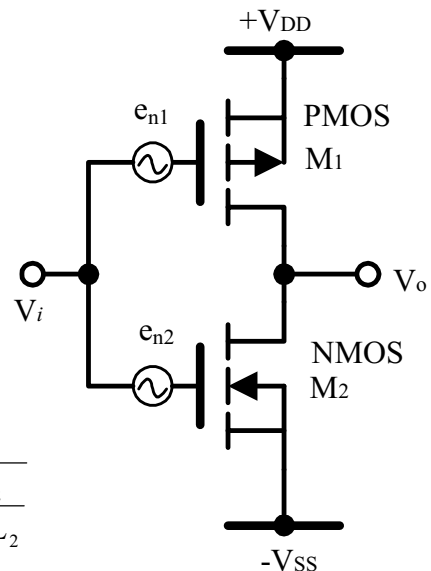
$$e_n(\text{IN}) = \frac{\sqrt{(g_{m1}e_{n1})^2 + (g_{m2}e_{n2})^2}}{g_{m1} + g_{m2}}$$

If  $g_{m1} = g_{m2}$

$$\Rightarrow e_n(\text{IN}) = \frac{1}{2} \sqrt{e_{n1}^2 + e_{n2}^2} = \frac{1}{2} \sqrt{\frac{a_{n1}}{W_1 L_1} + \frac{a_{n2}}{W_2 L_2}}$$

\* Larger size WL  $\Rightarrow$  smaller noise

If  $g_{m1} \neq g_{m2}$



$$\Rightarrow e_n(\text{IN}) = \sqrt{\frac{a_{n1}}{W_1 L_1} \left(1 + \frac{(\frac{\mu_n C_{ox}}{2})_2 a_{n2} L_2^2}{(\frac{\mu_p C_{ox}}{2})_1 a_{n1} L_1^2}\right)}$$
~~$$\left(1 + \sqrt{\frac{(\frac{\mu_n C_{ox}}{2})_2 W_2 L_1}{(\frac{\mu_p C_{ox}}{2})_1 W_1 L_2}}}\right)$$~~

\* Increase the channel length of the transistor having the highest  $a_n$  parameter.

Example : Bias current  $100\mu\text{A}$

Design I :  $M_1 : 1000\mu\text{m}/5\mu\text{m}$ ,  $M_2 : 400\mu\text{m}/4\mu\text{m}$

$$\Rightarrow e_n(\text{IN}) = 8.1\mu\text{V}(7.97\mu\text{V}) \quad 20\text{Hz} \sim 20\text{KHz}$$

Design II :  $M_1 : 1000\mu\text{m}/5\mu\text{m}$ ,  $M_2 : 200\mu\text{m}/8\mu\text{m}$

$$\Rightarrow e_n(\text{IN}) = 5.9\mu\text{V}(5.65\mu\text{V}) \quad 20\text{Hz} \sim 20\text{KHz}$$

Design III :  $M_1 : 500\mu\text{m}/10\mu\text{m}$ ,  $M_2 : 400\mu\text{m}/4\mu\text{m}$

$$\Rightarrow e_n(\text{IN}) = 10.5\mu\text{V}(10.36\mu\text{V})$$

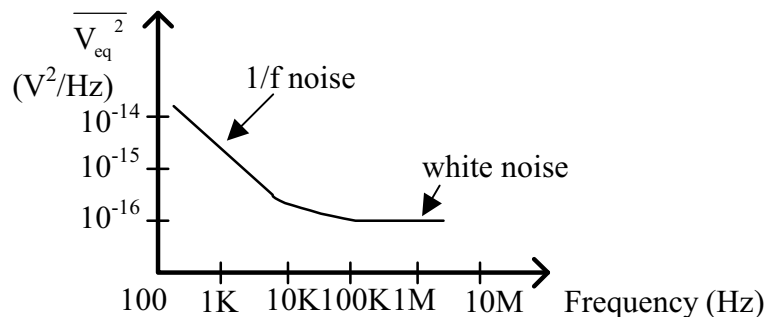
\* Best noise figure  $\Rightarrow$  highest  $W/L$  in PMOS

lowest  $W/L$  in NMOS

Note :  $WL$  for PMOS ( NMOS ) are the same.

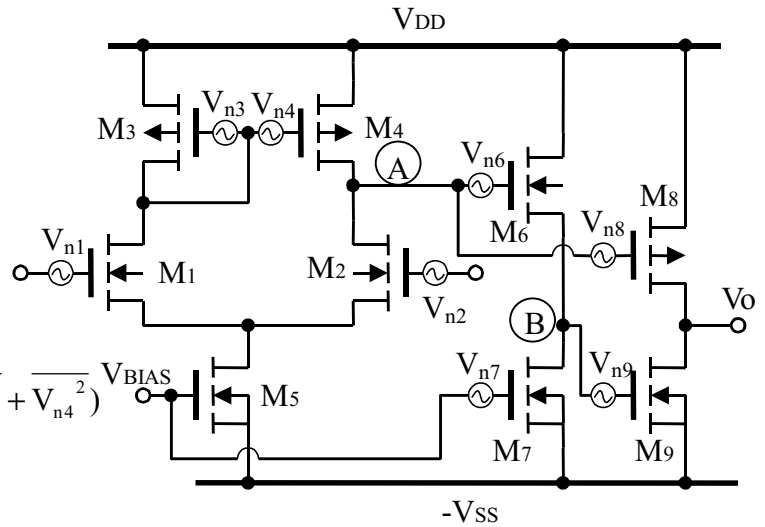
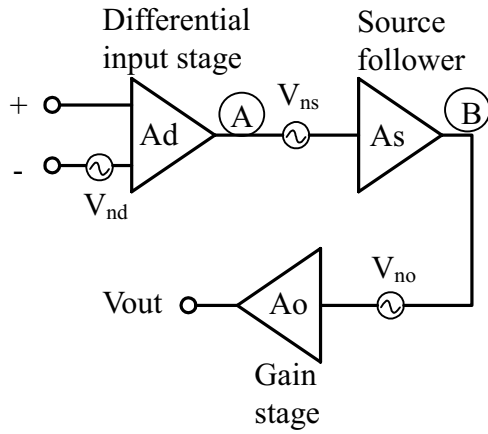
Reference : J.-C. Bertails, JSSC, vol.SC-14, pp.773-776, Aug.1979.

Noise spectrum of a typical MOSFET :



## §7-2.4 Noise performance of CMOS OP AMPs

### 1. Midband Analysis



$$\overline{V_{nd}^2} = \overline{V_{n1}^2} + \overline{V_{n2}^2} + \left(\frac{g_{m4}}{g_{m1}}\right)(\overline{V_{n3}^2} + \overline{V_{n4}^2})$$

$$\overline{V_{ns}^2} = \overline{V_{n6}^2} + (g_{m7}/g_{m6})^2 \overline{V_{n7}^2}$$

$$\overline{V_n^2} \approx \overline{V_{nd}^2} + \overline{V_{ns}^2} / A_d^2 = \overline{V_{n1}^2} + \overline{V_{n2}^2} + \left(\frac{g_{m4}}{g_{m1}}\right)^2 (\overline{V_{n3}^2} + \overline{V_{n4}^2}) + [\overline{V_{n6}^2} + (g_{m7}/g_{m6})^2 \overline{V_{n7}^2}] / A_d^2$$

\* At low frequency ( $< 1\text{KHz}$ ),  $1/f$  noise dominates and  $|A_d(\omega)| \gg 1$

$\Rightarrow \overline{V_{ns}^2}$  has a negligible effect on the OP noise.

The input stage dominates the overall noise contribution.

\* At high frequency where  $|A_d(\omega)| \approx \frac{g_{m7}}{g_{m6}} \gg 1$ , ( $\because M_6, M_7$  is a level

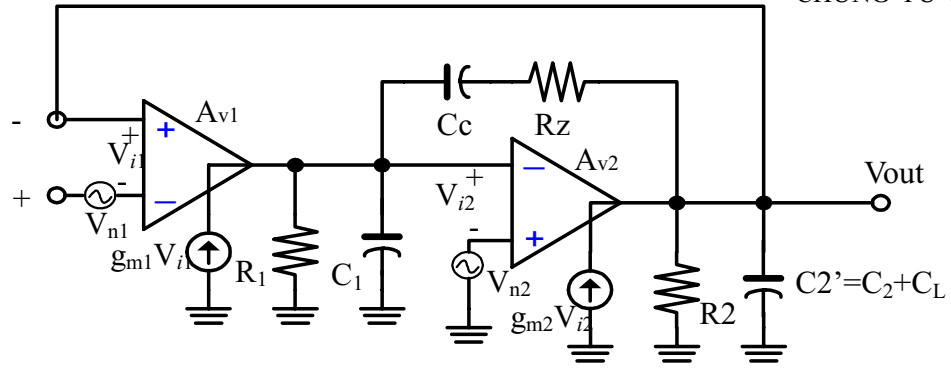
shifter,  $g_{m6}$  is small to obtain a large  $V_{Gs6} \Rightarrow \frac{g_{m7}}{g_{m6}} \gg 1$ ), the effect of

$V_{n7}$  is comparable to that of  $V_{n1}$  and  $V_{n2}$ . Thus  $M_7$  must be a low-noise device (like PMOS).

The effect of  $V_{no}$  is negligible on the total equivalent input noise voltage since the gain of the gain stage is very high.

### §7-2.5 High frequency analysis (for white noise)

For CMOS 2-stage OP AMP (without level shifter), the small-signal equivalent circuit is



(under unity-gain feedback)

$$\frac{V_{out}}{V_{in1}} = \frac{A_v [1 - sC_c (\frac{1}{g_{m2}} - R_z)]}{1 + A_v + as + bs^2 + cs^3}$$

$$\frac{V_{out}}{V_{in2}} = A_{v2} \frac{\{1 + s[C_c(R_1 + R_z) + C_1 R_1] + s^2 C_1 C_c R_1 R_z\}}{(1 + A_v) + as + bs^2 + cs^3}$$

when  $A_v = A_{v1} + A_{v2}$

$$a = C_c [A_v (\frac{1}{g_{m1}} - \frac{1}{g_{m2}} + R_z) + R_1 + R_2 + R_z] + C_1 R_1 + C_2' R_2$$

$$b = R_1 R_2 (C_1 C_2' + C_1 C_c + C_2' C_c) + R_z C_c (C_1 R_1 + C_2' R_2)$$

$$c = C_1 C_2' C_c R_1 R_2 R_z$$

Usually,  $|A_v| \gg 1$ ,  $R_z \ll R_1$ ,  $R_z \ll R_2$ ,  $C_1 \ll C_c$ ,  $C_1 \ll C_L$ , and  $C_2 \ll C_L$

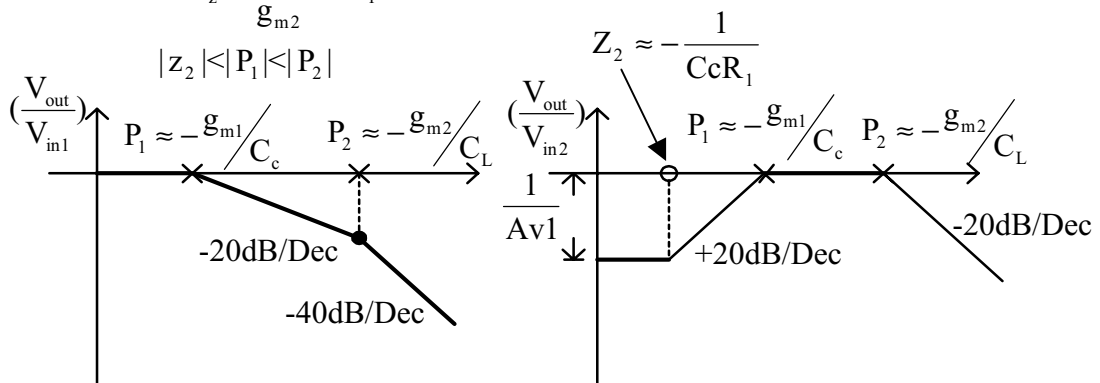
$$\Rightarrow \text{LHP Poleo : } P_1 \approx -\frac{g_{m1}}{C_c} ; P_2 \approx -\frac{g_{m2}}{C_L} , P_3 \approx -\frac{1}{C_1 R_z}$$

$$\text{RHP zero } (\frac{V_{out1}}{V_{in1}}) : z_1 = [C_c (\frac{1}{g_{m2}} - R_z)]^{-1} ;$$

$$\text{LHP zeros : } -\frac{1}{C_c R_1} = z_2 , z_3 \approx -\frac{1}{C_1 R_z} \quad (z_3 \rightarrow \infty)$$

$$\text{If } R_z = \frac{1}{g_{m2}} \Rightarrow z_1 = \infty$$

$$|z_2| < |P_1| < |P_2|$$



The equivalent noise bandwidths are

$$BW_1 = g_{m1} / 4C_c \quad (= |P_1| / 4)$$

$$BW_2 = g_{m2} / 4C_L - g_{m1} / 4C_c \quad (= |P_2| / 4 - |P_1| / 4)$$

$$\approx g_{m2} / 4C_L \quad (C_c \gg C_L)$$

$$\bar{V}_{\text{ntot}}^2 = \sum 4KT\gamma_i \frac{1}{g_{mi}} (BW_i) A_i, \quad \gamma_i = \text{constan } t (\approx \frac{3}{2})$$

( Consider only thermal noise )

$$= \frac{A_v}{1 + A_v} 4KT\gamma_1 \frac{1}{g_{m1}} (g_{m1} / 4C_c) + \frac{A_{v2}'}{1 + A_v} 4KT\gamma_2 \frac{1}{g_{m2}} (g_{m2} / 4C_L)$$

$$= \frac{A_v}{1 + A_v} \gamma_1 \frac{KT}{C_c} + \frac{A_{v2}'}{1 + A_v} \gamma_2 \frac{KT}{C_L}$$

where  $A_{v2}'$  and  $A_v'$  are average gains between  $P_1$  and  $P_2$ .

- \* The total white noise of the OP AMP is inversely proportional to  $C_c$  and  $C_L$ .
- \* Due to the foldover effect in SCF, white noise ( thermal noise ) becomes important.
- \* 1) Clock feedthrough noise; 2) noises coupled from the power supplies, clock, and ground lines, and from the substrate; 3) white noise and flicker noise generated in the switches and OP AMPs are three major noise sources in the switched-capacitor circuits.

### §7-2.6 Dynamic range of OP AMPs

$V_{\text{in,max}}$  : the maximum input voltage which an OP AMP can handle without generating an excess amount of nonlinear distortion.

$V_{\text{in,min}}$  : the minimum input signal voltage which still does not drown in noise and distortion.

$$\text{Dynamic range} \equiv 20 \log_{10} \left( \frac{V_{\text{in,max}}}{V_{\text{in,min}}} \right)$$

For an open-loop OP AMP,

$$V_{in,max} \approx \frac{V_{cc}}{A_d}$$

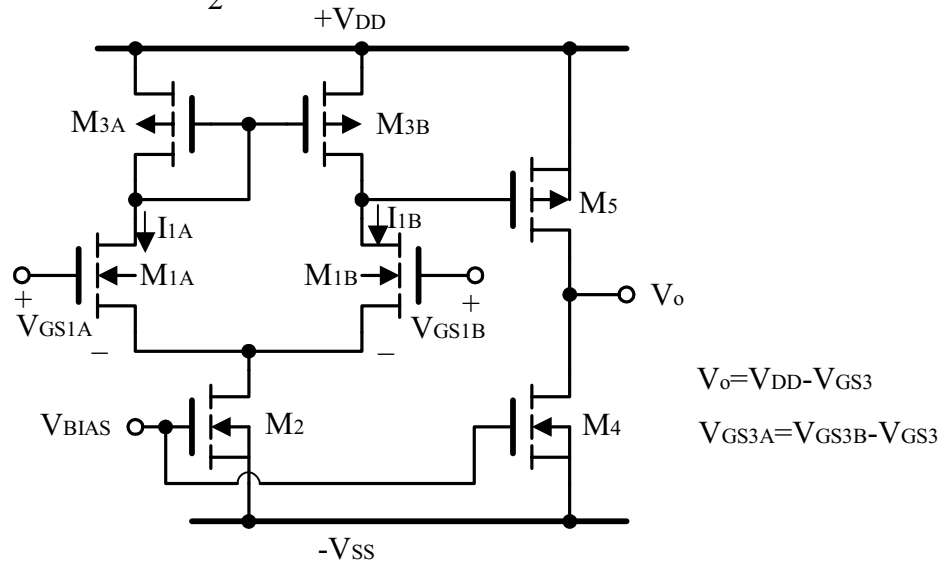
$$V_{in,min} \approx \sqrt{V_n^2}$$

⇒ Dynamic range  $\approx 30 - 40\text{dB}$ .

### §7-3 Practical Design Consideration on Offset

#### §7-3.1 Input offset voltage of a CMOS OP AMP

1). Random offset  $K \equiv \frac{C_{ox}\mu}{2}$



$$V_{OS} \equiv V_{GS1A} - V_{GS1B} = \left[ \frac{2}{K_{N1A}} \left( \frac{L}{W} \right)_{1A} I_{1A} \right]^{\frac{1}{2}} - \left[ \frac{2}{K_{N1B}} \left( \frac{L}{W} \right)_{1B} I_{1B} \right]^{\frac{1}{2}} + V_{TH1A} - V_{TH1B}$$

$$= \Delta V_{TH1} + \left( \frac{2}{K_N} I_1 \right)^{\frac{1}{2}} \left[ \left( \frac{L_1 + \frac{\Delta L_1}{2}}{W_1 + \frac{\Delta W_1}{2}} \right)^{\frac{1}{2}} - \left( \frac{L_1 - \frac{\Delta L_1}{2}}{W_1 - \frac{\Delta W_1}{2}} \right)^{\frac{1}{2}} \right] + \dots$$

$$\cong \Delta V_{TH1} + \left( \frac{2}{K_N} I_1 \frac{L_1}{W_1} \right)^{\frac{1}{2}} \left[ \left( 1 + \frac{1}{2} \frac{\Delta L}{2L_1} \right) \left( 1 - \frac{1}{2} \frac{\Delta W}{2W_1} \right) - \left( 1 - \frac{1}{2} \frac{\Delta L}{2L_1} \right) \left( 1 + \frac{1}{2} \frac{\Delta W}{2W_1} \right) \right] + \dots$$

$$\cong \Delta V_{TH1} + \left( \frac{2}{K_N} I_1 \frac{L_1}{W_1} \right)^{\frac{1}{2}} \left( \frac{\Delta L}{2L_1} - \frac{\Delta W}{2W_1} \right) - \left( \frac{2}{K_N} I_1 \frac{L_1}{W_1} \right)^{\frac{1}{2}} \left( \frac{\Delta K_N}{2K_N} \right) + \left( \frac{2}{K_N} I_1 \frac{L_1}{W_1} \right)^{\frac{1}{2}} \left( \frac{\Delta I}{2I_1} \right)$$

$$A \equiv \frac{A_1 + A_2}{2} \quad \Delta A \equiv A_1 - A_2$$

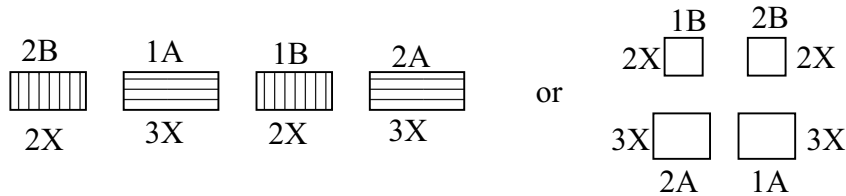
$$\begin{aligned} \Delta I &= I_{1A} - I_{1B} = \frac{K_{P3A}}{2} \left( \frac{W}{L} \right)_{3A} (V_{GS3} - V_{TH3A})^2 - \frac{K_{P3B}}{2} \left( \frac{W}{L} \right)_{3B} (V_{GS3} - V_{TH3B})^2 \\ &= \frac{K_P}{2} \frac{W_3}{L_3} (V_{GS3} - V_{TH3})^2 \left( \frac{\Delta K_P}{K_P} + \frac{\Delta W_3}{W_3} - \frac{\Delta L_3}{L_3} - \frac{2\Delta V_{TH3}}{V_{GS3} - V_{TH3}} \right) \\ &= I_1 \left( \frac{\Delta K_P}{K_P} + \frac{\Delta W_3}{W_3} - \frac{\Delta L_3}{L_3} - \frac{2\Delta V_{TH3}}{V_{GS3} - V_{TH3}} \right) \\ \Rightarrow V_{OS} &= \Delta V_{TH1} + \left( \frac{2}{K_N} I_1 \frac{L_1}{W_1} \right)^{\frac{1}{2}} \left[ \frac{\Delta L_1}{2L_1} - \frac{\Delta W_1}{2W_1} - \frac{\Delta K_N}{2K_N} + \frac{\Delta K_P}{2K_P} + \frac{\Delta W_3}{2W_3} - \frac{\Delta L_3}{2L_3} - \frac{\Delta V_{TH3}}{V_{GS3} - V_{TH3}} \right] \\ &\cong \Delta V_{TH1} + (V_{GS1} - V_{TH1}) \left( \frac{\Delta W_3}{2W_3} + \frac{\Delta L_1}{2L_1} \right) - \left( \frac{K_P}{K_N} \frac{W_3}{W_1} \right)^{\frac{1}{2}} \Delta V_{TH3} \quad \left( \text{If } \frac{\Delta L_3}{2L_3}, \frac{\Delta W_1}{2W_1} \rightarrow 0 \right) \end{aligned}$$

2). Systematic offset.  $V_{OS} = \frac{V_{Odc}}{A_O}$  where  $V_{Odc} \neq 0$  and  $A_O$  is the dc gain of the OP AMP.

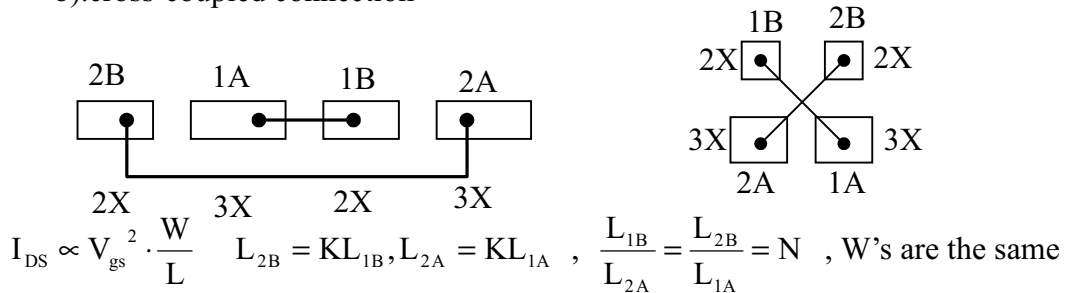
### 7-3.2 Low offset design techniques for CMOS OP AMPS

1. Layout techniques to reduce the random offset.

a). linear variation of devices across a row of transistor or a matrix of transistors.



b). cross-coupled connection



Cross-coupled:  $I_{DS1A} + I_{DS1B} = I_{DS2A} + I_{DS2B}$

$$\frac{V_{GS1}^2}{L_{1A}} + \frac{V_{GS1}^2}{L_{1B}} = \frac{V_{GS2}^2}{L_{2A}} + \frac{V_{GS2}^2}{L_{2B}} \Rightarrow \frac{V_{GS1}}{V_{GS2}} \cong \sqrt{\frac{1+KN}{K+N}}$$

If  $K=1 \Rightarrow$  precision channel length control  $\Rightarrow \frac{V_{GS1}}{V_{GS2}} \cong 1 \Rightarrow$  Ordered dimension

error  $\cong 0 \Rightarrow V_{OS} \cong 0$

$$\text{If } K=1.1, N=1.1 \quad \rightarrow \quad \frac{V_{GS1}}{V_{GS2}} = 1.0023$$

But for single-pair design (1B, 2B, or 1A, 2A)

$$\frac{V_{GS1}}{V_{GS2}} = \sqrt{K} = \sqrt{1.1} = 1.049 \quad \text{larger } V_{GS} \text{ error} \rightarrow \text{larger } V_{OS}$$

Ref: RCA Review, vol. 39, pp.250-277, June 1978.

c) Common-centroid structures to reduce  $\Delta V_{TH}$

Ref: IEEE JSSC, vol. SC-13, pp.791-798, Dec. 1978

IEEE JSSC, vol. SC-16, pp.661-668, Dec. 1981

## 2. General optimum matching rules to reduce the random offset

- |                          |                               |
|--------------------------|-------------------------------|
| 1. Same structure        | 5. common-centroid geometries |
| 2. Same temperature      | 6. Same orientation           |
| 3. Same shape, same size | 7. Same surroundings          |
| 4. Minimum distance      | 8. Non minimum size           |

Ref.: IEEE JSSC, vol. SC-20, pp.657-665, June 1985

## 3. Low $V_{GS} - V_{TH1}$ to reduce the dimensional random offset

## 4. Dimension design to eliminate the systematic offset

$$\frac{(W/L)_{3A}}{(W/L)_5} = \frac{(W/L)_{3B}}{(W/L)_5} = \frac{1}{2} \frac{(W/L)_2}{(W/L)_4} \quad \rightarrow \quad V_{odc} = 0 \quad \rightarrow \quad \text{systematic offset} \approx 0$$

To avoid the process-induced variations in channel lengths, we usually choose  $L_5 = L_{3A} = L_{3B}$ . But this design will enhance the noise contribution from the PMOS  $M_{3A}, M_{3B}$  (NMOS  $M_{3A}, M_{3B}$  for PMOS-input structure).

$\rightarrow$  A compromise is required.

## 5. Sample-data techniques to eliminate the offset voltage.

Ref.: IEEE JSSC, p.499, Aug. 1978

IEEE JSSC, vol. SC-10, pp.371-379, Dec. 1975

IEEE JSSC, vol. SC-20, pp.805-807, June. 1985

IEEE JSSC, vol. SC-17, pp.1008-1013, Dec. 1986

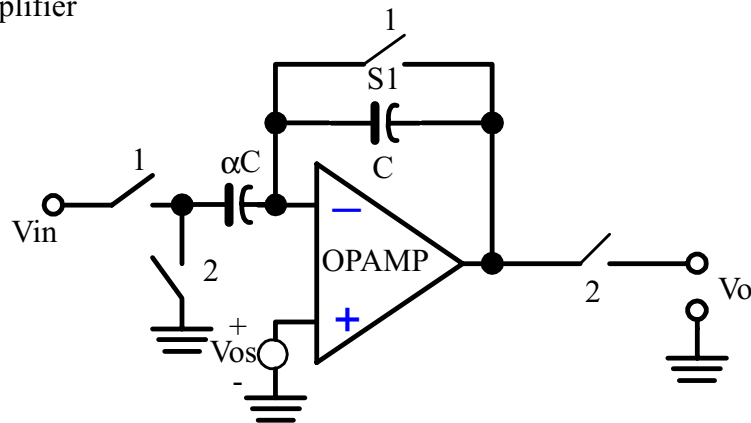
IEEE JSSC, vol. SC-16, pp.745-748, Dec. 1981

IEEE JSSC, pp.837-844, Aug. 1985

Applications: Zero-offset OP AMPs, High-precision comparators,  
Instrumentation amplifiers, High-precision amplifiers,  
Switched-capacitor amplifier, Switched-capacitor network.

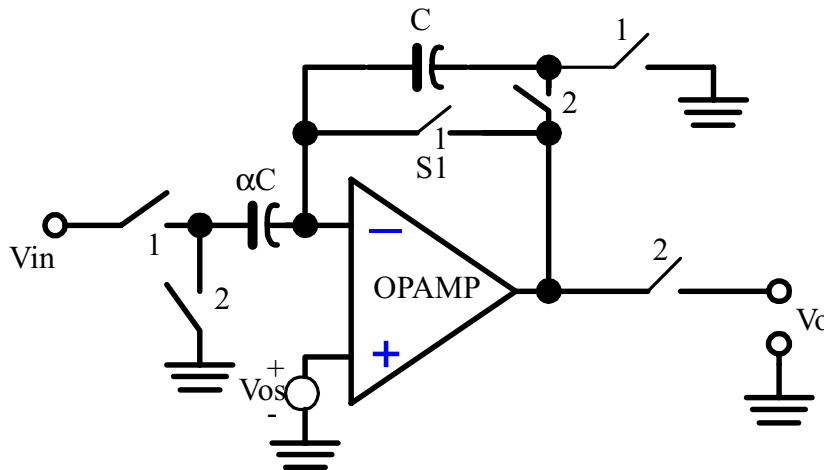
1) Offset cancellation in OP-AMP-based switched-capacitor(SC) amplifier

(1) SC amplifier

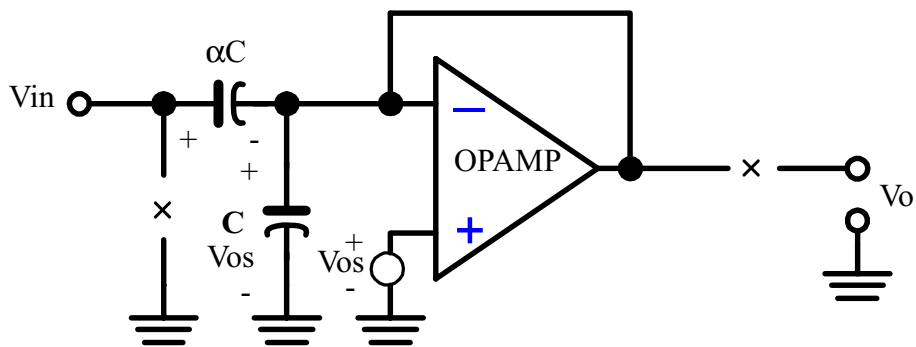


$$\frac{V_{in}\alpha C}{C} + V_{os} = V_o \quad \Rightarrow \quad \frac{V_o}{V_{in}} = \alpha + \frac{V_{os}}{V_{in}}$$

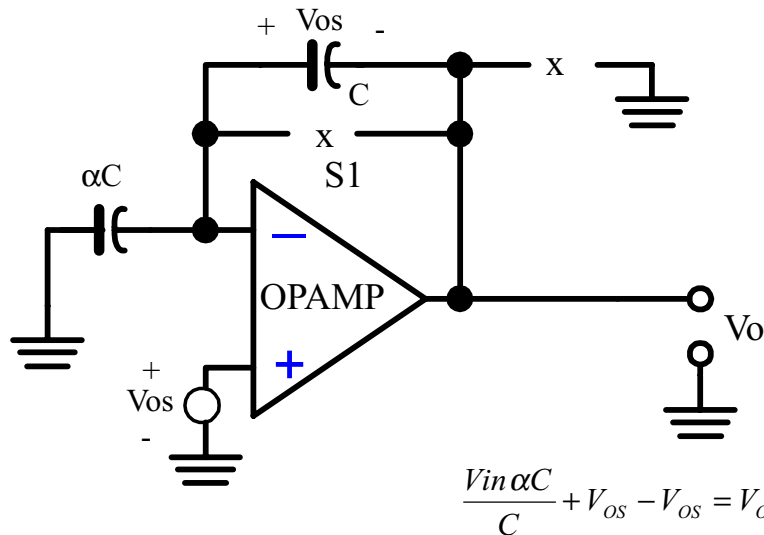
(2) Modified SC Amplifier



Step 1: Switch 1 ON, Switch 2 OFF:

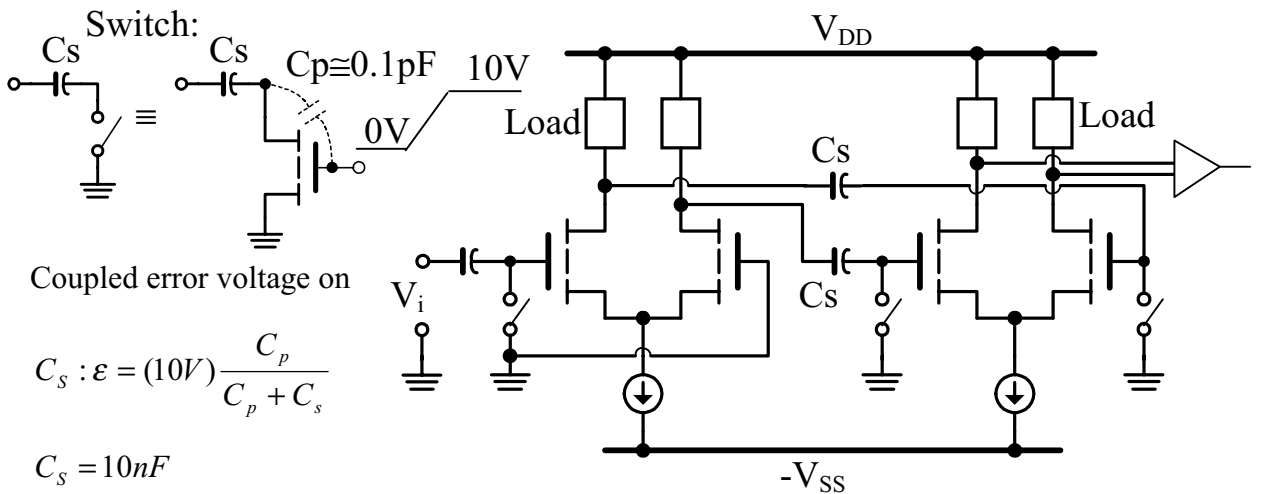


Step 2: Switch 2 ON, Switch 1 OFF:



\*The charge injection error of the switched S1 cannot be eliminated.

2) Offset cancellation in precision amplifier



$C_s = 10nF$

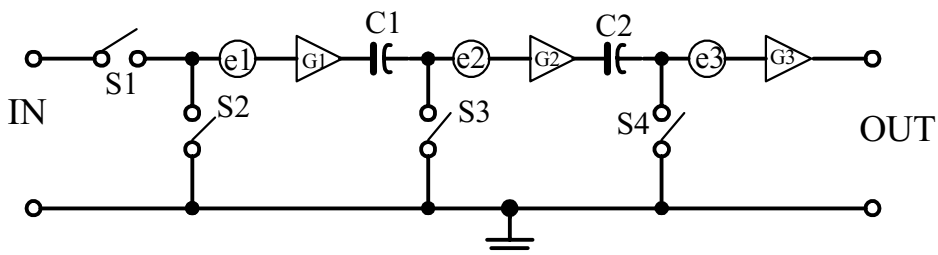
$\Rightarrow \varepsilon = 10V \frac{0.1pF}{0.1pF + 10000pF}$   
 $= 100\mu V$

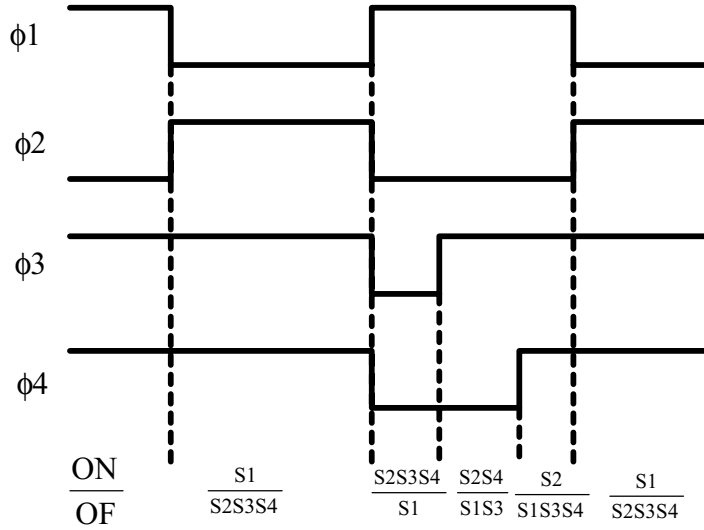
$C_s \uparrow \varepsilon \downarrow$

or using the differential outputs rather than the single output to eliminate the common mode voltage  $\varepsilon$

- \* amplifier with offset voltage memorization
- \* residual voltage successive memorization (RSM) amplifier
- \* auto-zero design
- \* chopper-stablized design
- ✳ capable of reducing the offset voltage by 1~4 order of magnitude

RSM amplifier(P-MOSFETs)





$$V_{off} = (e_n + \epsilon_n) / G_1 G_2 \dots G_{n-1}$$

$e_n$  : input offset voltage

$\epsilon_n$  : parasitic clock error pulse  
of the nth stage